## Towards Quantifying Defect Density in Molybdenum Disulfide (MoS<sub>2</sub>) via Optical Emission Spectroscopy

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Monolayer molybdenum disulfide ( $MoS_2$ ) absorbs and emits light via a direct optical bandgap, making it a promising material for many optoelectronic applications. While metal-organic chemical vapor deposition (MOCVD) is a scalable method for producing monolayer MoS<sub>2</sub>, the optical emission of material produced in this manner is lower compared to the mechanical exfoliated  $MoS_2$  due to high defect density. In this study, uniform monolayer  $MoS_2$  films were grown on a 2-inch sapphire substrate. Optical characterization reveals that thermal annealing at temperatures up to 340 °C in the atmosphere enhances the optical emission of MoS<sub>2</sub> grown in N<sub>2</sub>, increasing PL intensity by a factor of three, while changing from dominant Trion emission to a more neutral exciton one. We propose that during the annealing sulfur vacancies are passivated by oxygen atoms. This reduces the number of excess electrons, leading to lower background n-doping and reduced nonradiative Auger losses [1]. Low temperature (5.5 K) PL measurements support the hypothesis of defect annealing: Deep defect emission dominates the spectrum for the as-grown sample, while annealing leads to near bandgap emission. These empirical observations lay a foundation for scalable techniques for quantifying defect concentration of MOCVD-grown MoS<sub>2</sub> based on the "observed" optical emission changes. A Bayesian model will incorporate prior information about defects in MOCVD MoS2 and a likelihood function that accounts for defect distribution and associated uncertainties, yielding posterior probabilities of defect occurrence. Overall, this study investigates the post-growth treatment of MoS<sub>2</sub> and presents a scalable approach to improving its optical emission and defect quantification, advancing its potential for optoelectronic applications.

## Reference

[1] Nan et al., ACS nano, 6 (2014) 5738-5745 Figures



Figure 1: Room-temperature PL spectra of  $MoS_2$  samples treated at 240°C and 340°C in the atmosphere. The inset shows PL spectra of  $N_2$ -grown  $MoS_2$  under the same thermal treatments, measured at 5.5K.